



1746
Jfw

PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Application No. : **10/040,042** Confirmation No. **1835**
Applicant : **Wei-Yu Su**
Filed : **November 7, 2001**
TC/A.U. : **1746**
Title : **Method for Reduction of Photomask Defects**

Docket No. : **N1085-90003**
Customer No. : **08933**

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

CERTIFICATE OF MAILING,
37 C.F.R. §1.8(a)
I certify that this correspondence and the
enclosures mentioned therein are being deposited
by First Class U.S. Mail with sufficient postage on
the date shown below, addressed to Commissioner
for Patents, PO Box 1450, Alexandria, Virginia
22313-1450

Richard A. Paikoff
Richard A. Paikoff, Reg. No. 34,892

6/8/04
Date

AMENDMENT AND RESPONSE

Sir:

In response to the Office Action of March 9, 2004, please amend the above-identified application as follows:

Amendments to the Specification begin on page 2 of this paper.

Amendments to the Claims are reflected in the listing of claims which begins on page 4 of this paper.

Amendments to the Drawings begin on page 8 of this paper and include both an attached replacement sheet and an annotated sheet showing changes.

Remarks begin on page 9 of this paper.